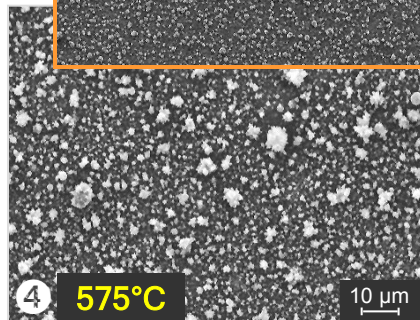
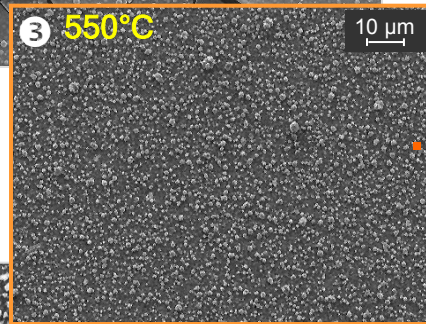
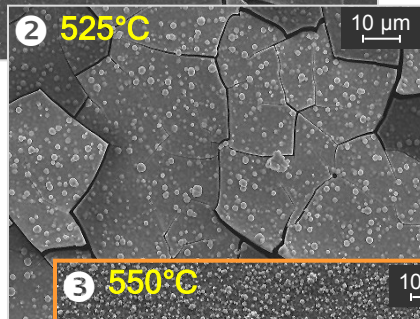
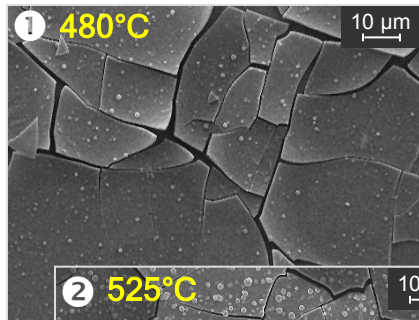


Influence of the substrate temperature



Distance: 27 mm., flow rate: 1.17 ml/h, time: 60 min.

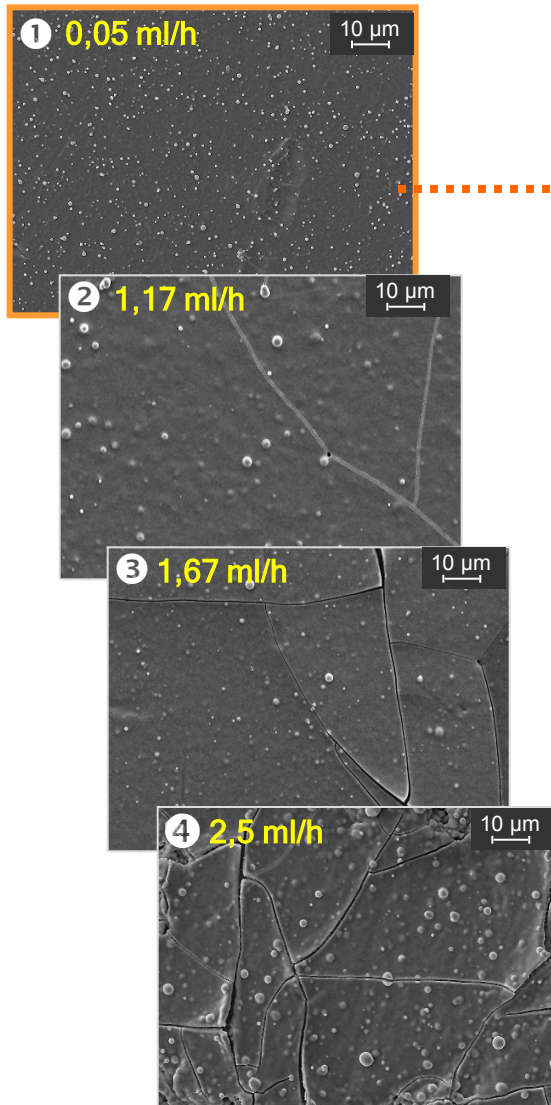
Temperature too low (① et ②): dense film but cracked due to stresses during the drying step (solvent excess)

Appropriated temperature - ③

Equilibrium between quantity of arriving solvent and evaporation

Temperature too high (④): arriving droplets too dried to spread leading to porous film (not enough solvent)

Influence of the solution flow rate



Distance: 47 mm, temperature: 450°C, time: 60 min.

Flow rate appropriated - ①

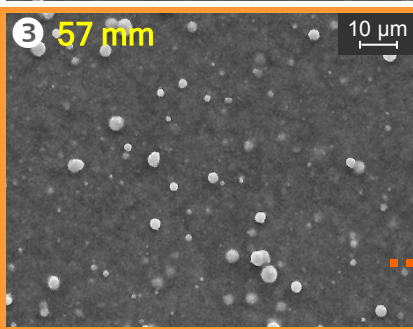
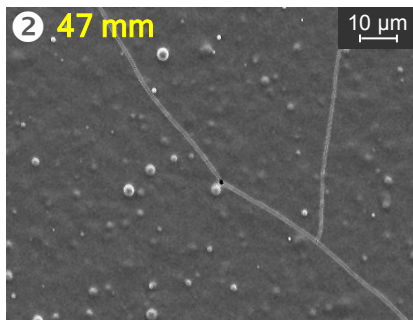
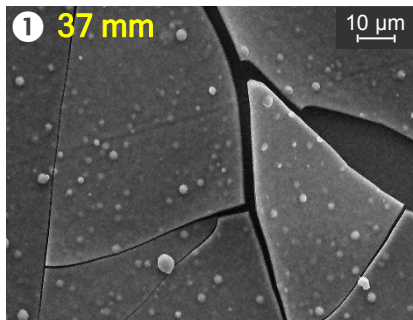
The lower the flow rate, the denser the film with no cracks

Flow rate too high: wetter film and cracked (②, ③ et ④).

$$* d = 3.78\pi^{\frac{-2}{3}} Q^{\frac{1}{2}} \left(\frac{\rho\varepsilon_0}{\nu\lambda} \right)^{\frac{1}{6}} f_b$$

*Ganan-Calvo- Physical Review Letters 79 (2) 1997 pp. 217-220

Influence of nozzle to substrate distance



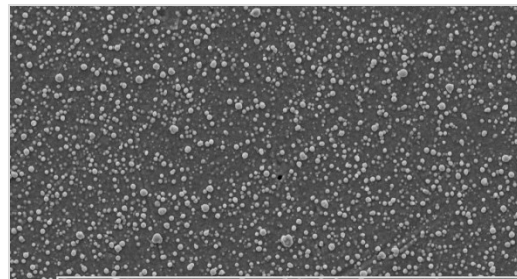
Temperature: 450°C, flow rate: 1.17 ml/h, time: 60 min.

Distance too short : arriving dropets too wet and films cracks (① et ②).

Appropriated distance - ③

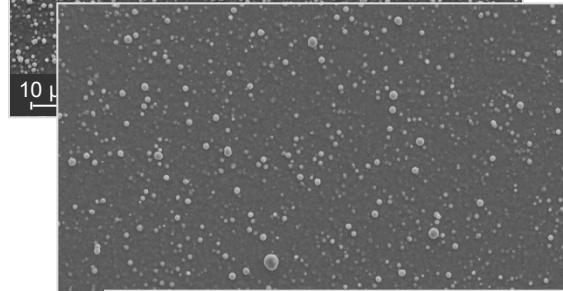
A larger distance favors the evaporation of solvent in excess
no cracks

Correlation temperature – working distance

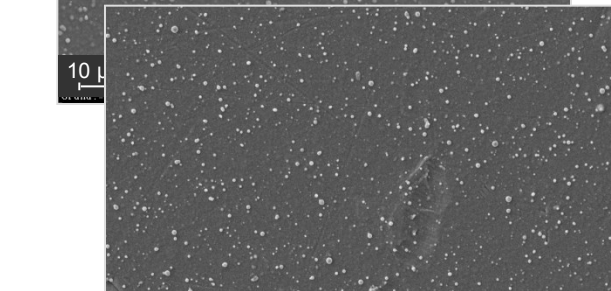


Flow rate: 0.05 ml/h, time: 60 min.

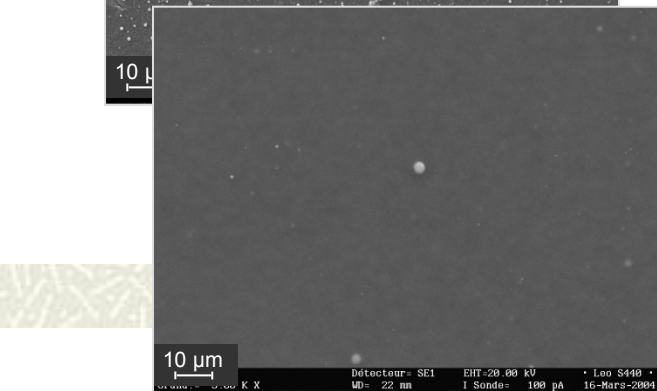
D=27 mm, T=520°C



D=37 mm, T=450°C



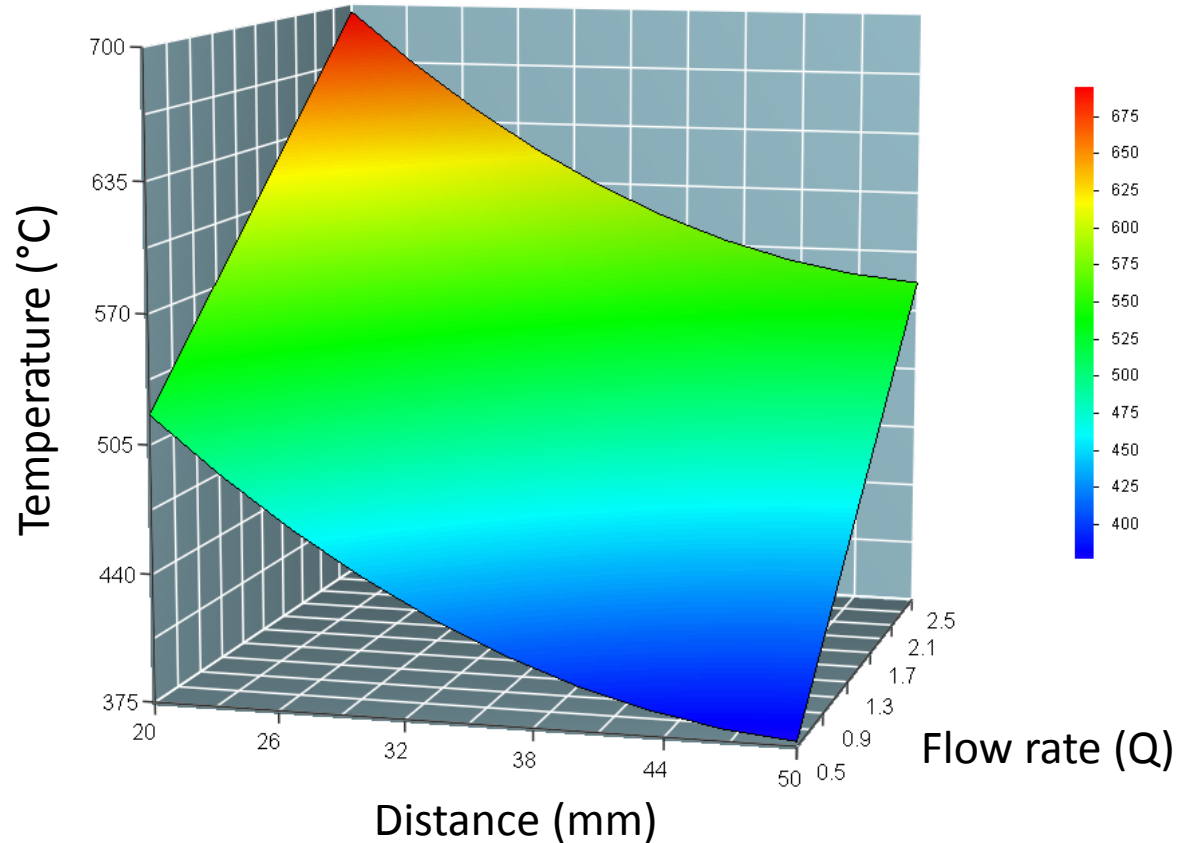
D=47 mm, T=400°C



D=57 mm, T=375°C

Correlation of process parameters

Flow rate (Q) - Distance (D) - Temperature (T)



$Q \uparrow$ et $D \downarrow \longrightarrow T_s \uparrow$

Microstructural characterization - SEM

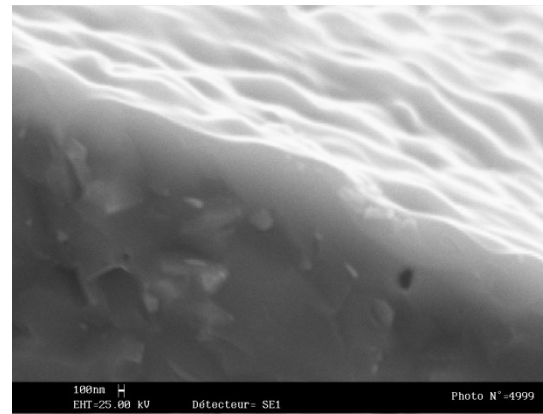
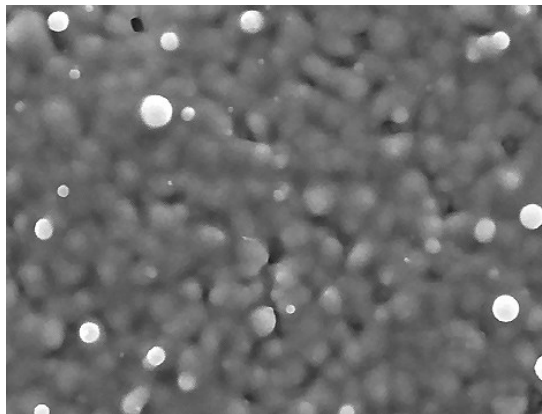
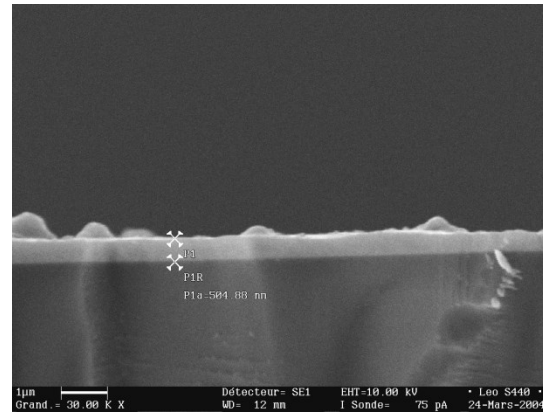
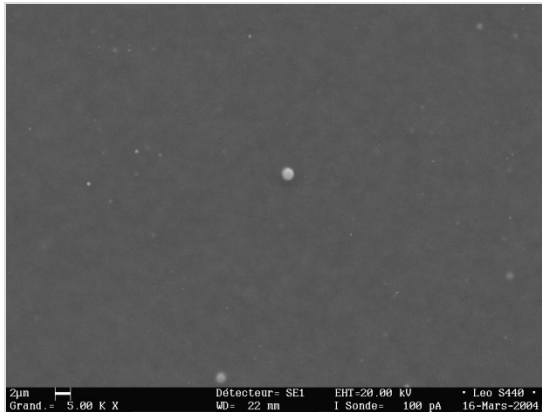
Dense thin films of cubic and tetragonal zirconia

Solution
(Zr(acac)₄ · 10H₂O + 10% m YCl₃ · 6H₂O)
in BC - ethanol 1:1

375°C, 57 mm, 0.5 ml/h
60 min.

thickness : ≈ 300 nm

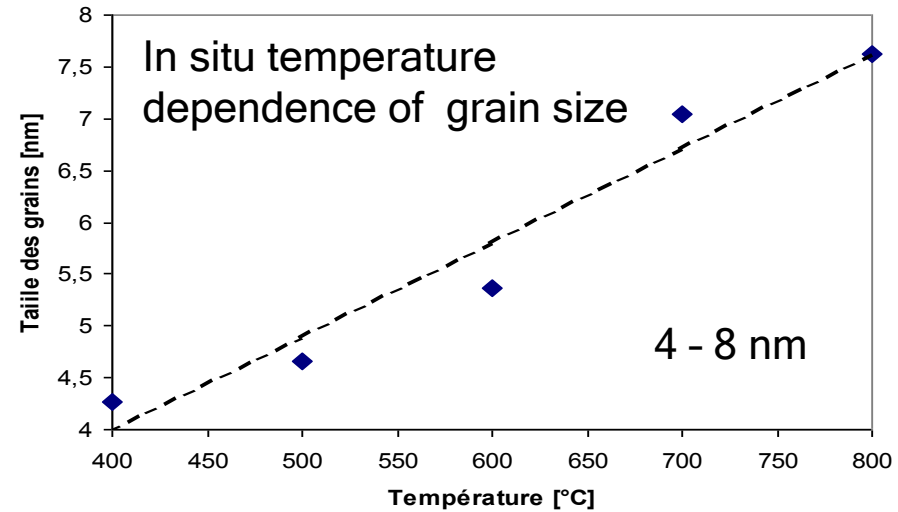
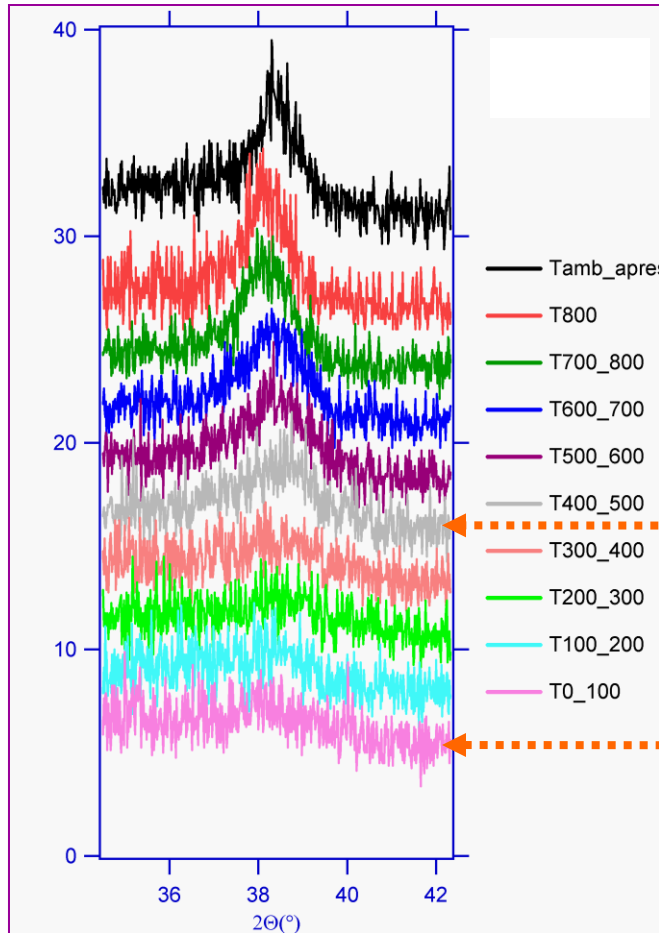
on glass



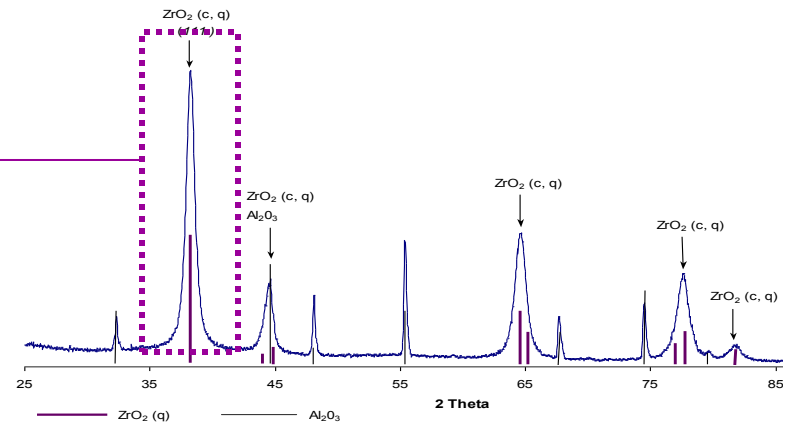
on composite NiO-8YSZ

Crystallization of films and grain growth

Tetragonal zirconia annealed up to 800°C, 1h30', **in situ XRD**

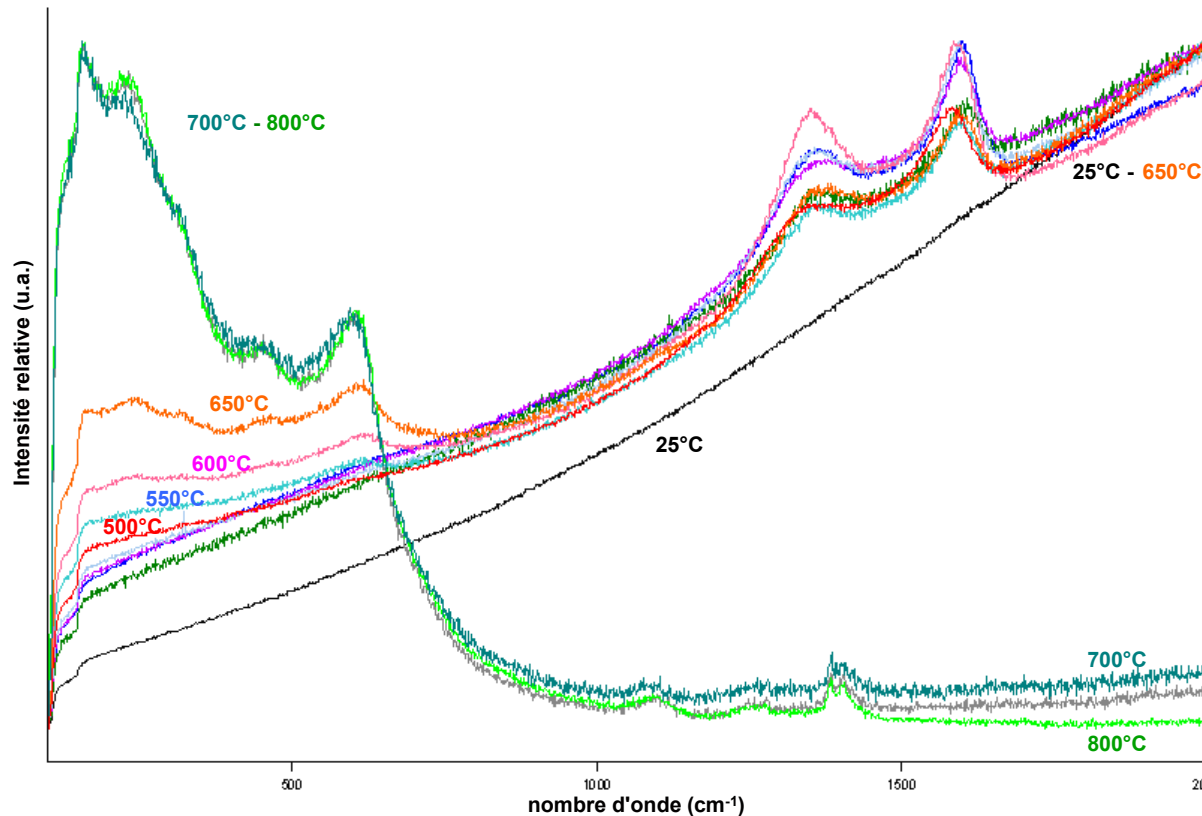


Crystallization at 500°C



Amorphous raw films

Temperature dependence of 8YSZ thin film In situ Raman spectroscopy



$T \leq 650^{\circ}\text{C}$

Organic residues
present in the film

$T \geq 700^{\circ}\text{C}$

Full decomposition
of organic residues

- Cubic 8YSZ spectrum visible from 550°C.

Neagu R., Perednis D., Princiville A., Djurado E., *Surface and Coatings Technology* 200 [24] (2006) 6815-6820

Neagu R., Perednis D., Princiville A., Djurado E., *Solid State Ionics* 177 [19-25] (2006) 1981-1984

Neagu R., Djurado E., Ortega L., Pagnier T., *Solid State Ionics* 177 [17-18] (2006) 1443-1449

Conclusions ...

- Investigation of ESD process parameters on the microstructure of doped zirconia films (substrate temperature, nozzle to substrate distance, flow rate) → **Optimal ESD conditions** for the synthesis of dense and nanostructured thin films of YSZ and TZP (300 nm in thickness).
- Determination of single phased tetragonal and cubic films and crystallization temperature (500-650°C) by *in situ* temperature dependence XRD and Raman spectroscopy

Outline

1 - Sonochemistry for the synthesis of controlled nanostructured oxide powders: zirconia and ceria-based oxides

- » Ultrasonic Spray Pyrolysis (USP) process – DOE
- » ZrO₂ - based powders: morphology and phase transitions
- » Physico-chemical properties of CGO powders and sintering behavior
- » USP advantages and disadvantages

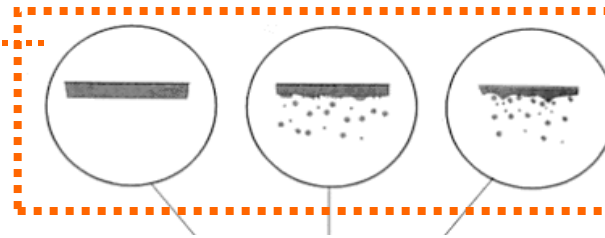
2 – Electrostatic Spray Deposition for the design of dense and porous films

- » Electrostatic Spray Deposition (ESD) process
- » Optimization study of the ESD process to coat thin dense zirconia-based films
- » **Fundamental study of the formation of the ESD layer**
- » Advanced oxygen electrodes for SOC:
LSCF, CCO, LSM, LSM/YSZ, LPNO
- » ESD advantages and disadvantages

FUNDAMENTAL STUDY OF THE FORMATION OF THE ESD LAYER

Two phenomena:

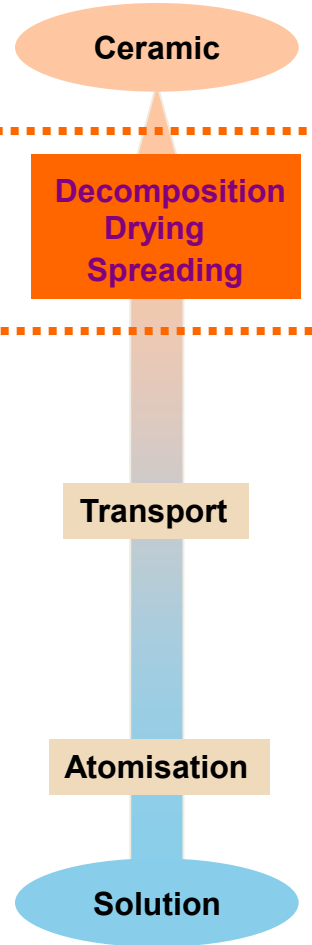
- Spreading and drying of droplets



Combined mechanism → dense (under)layer spreading/evaporation/precipitation

- Film growth

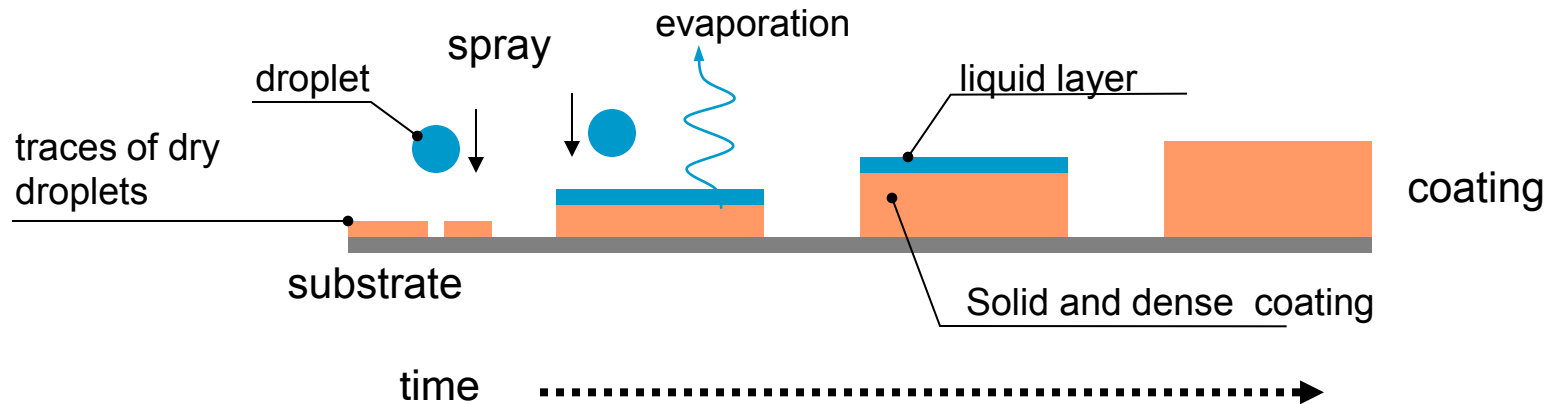
Preferential landing → porous film



Growth of a dense layer

- In the **ideal** case (droplets of the same size, no particles)
- Coating only by spreading - evaporation - precipitation.

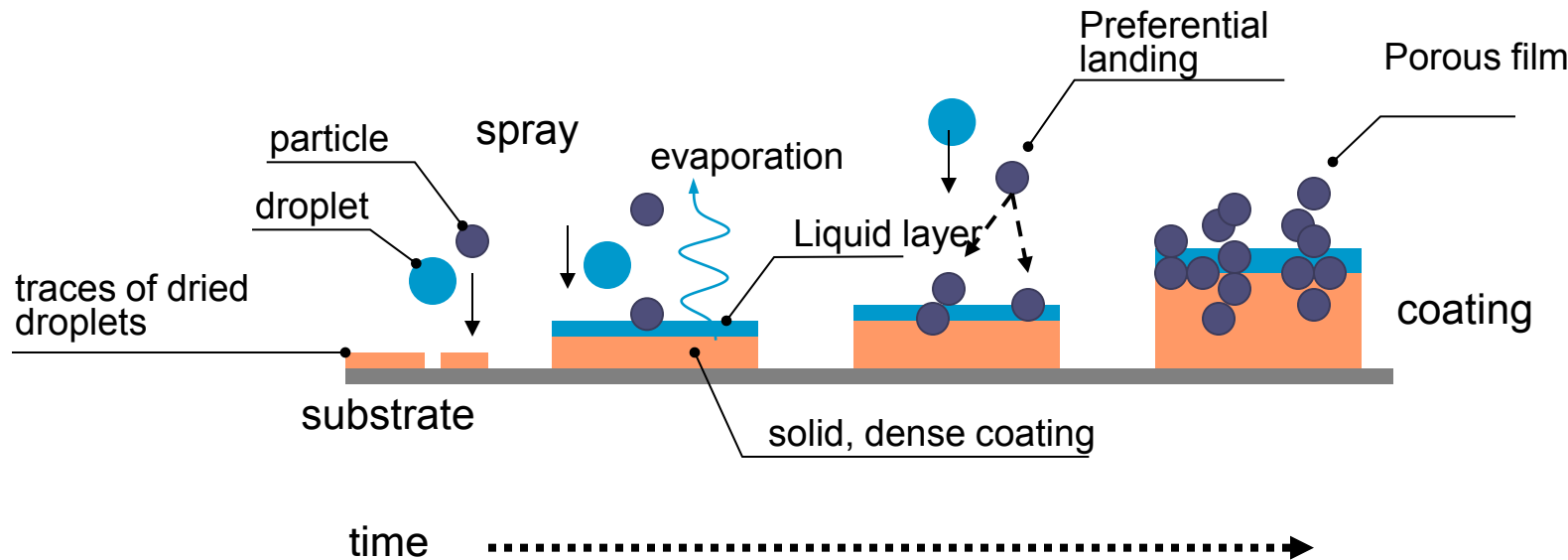
A perfect coating is expected



equilibrium impacting solvent/evaporating solvent

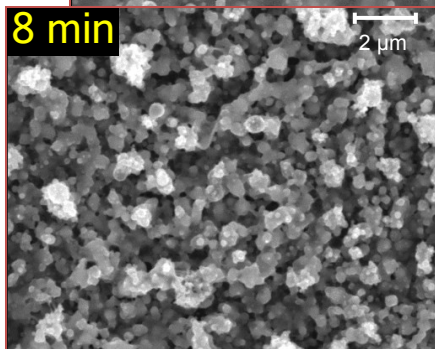
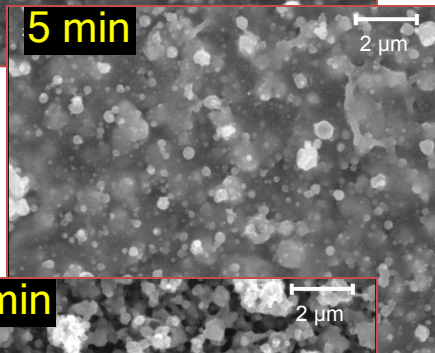
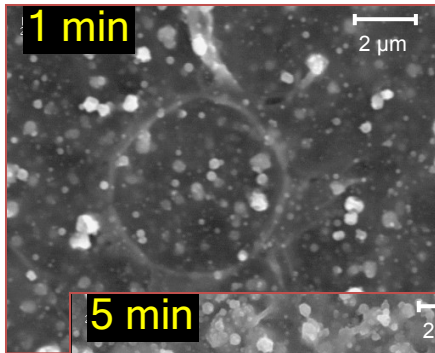
Growth of a porous layer

- For a **multi-jet** atomisation cone, (mixture of droplets and particles) the coating is consisted of 2 layers:
 - A dense sub-layer, formed by spreading- evaporation - precipitation of large droplets,
 - A porous layer above, due to preferential landing of particles and droplets.

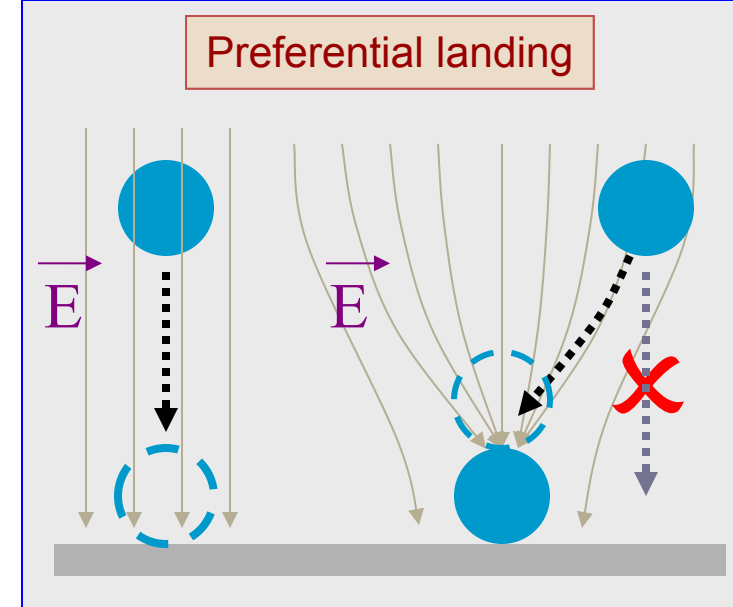


Preferential landing

SEM observations:



400°C



Roughness of the coating increases versus time. The porous film is formed due to the impacting particles (drying droplets during the transport)



After a sufficient deposition time, the microstructure is no more the result of the evaporation - precipitation but the effect of the preferential landing.

Outline

1 - Sonochemistry for the synthesis of controlled nanostructured oxide powders: zirconia and ceria-based oxides

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- » ZrO_2 - based powders: morphology and phase transitions
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2 – Electrostatic Spray Deposition for the design of dense and porous films

- » Electrostatic Spray Deposition (ESD) process
- » Optimization study of the ESD process to coat thin dense zirconia-based films
- » Fundamental study of the formation of the ESD layer
- » **Advanced oxygen electrodes for SOC:
LSCF, CCO, LSM, LSM/YSZ, LPNO**
- » ESD advantages and disadvantages

Advanced oxygen electrodes for SOC

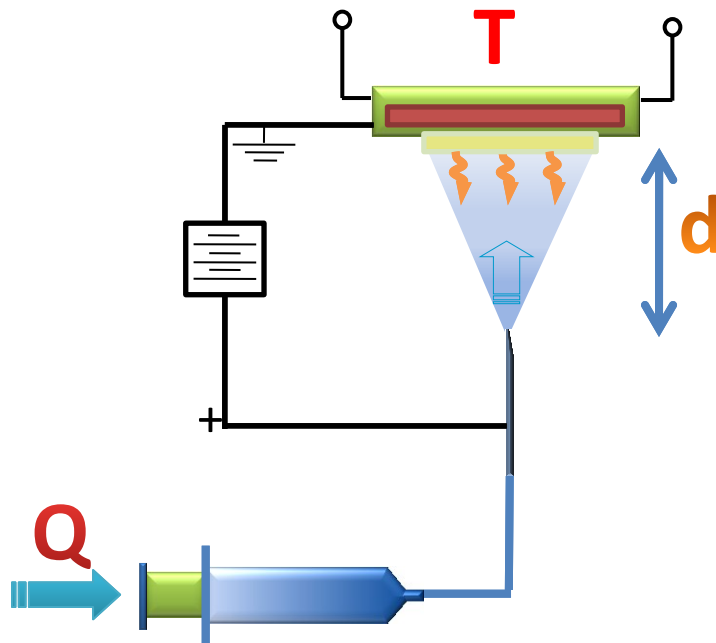
Porous LSCF6428 films

$\text{Ce}_{0.9}\text{Gd}_{0.1}\text{O}_{2-\delta}$ substrates

- Isostatic pressing (Praxair powders)
- Sintering @ 1450 °C / 4h in air
- $\varnothing = 18 \text{ mm}$ / ~1 mm thick
- $\rho_r \geq 95 \%$

$\text{La}_{0.6}\text{Sr}_{0.4}\text{Co}_{0.2}\text{Fe}_{0.8}\text{O}_{3-\delta}$ solution

- $\text{La}(\text{NO}_3)_2$, SrCl_2 , $\text{Co}(\text{NO}_3)_2$ and $\text{Fe}(\text{NO}_3)_2$ mixed in
 - EtOH:BC (1:2 vol.%)
 - EtOH:H₂O (1:5 vol.%)
- Concentration = 0.02 mol/L



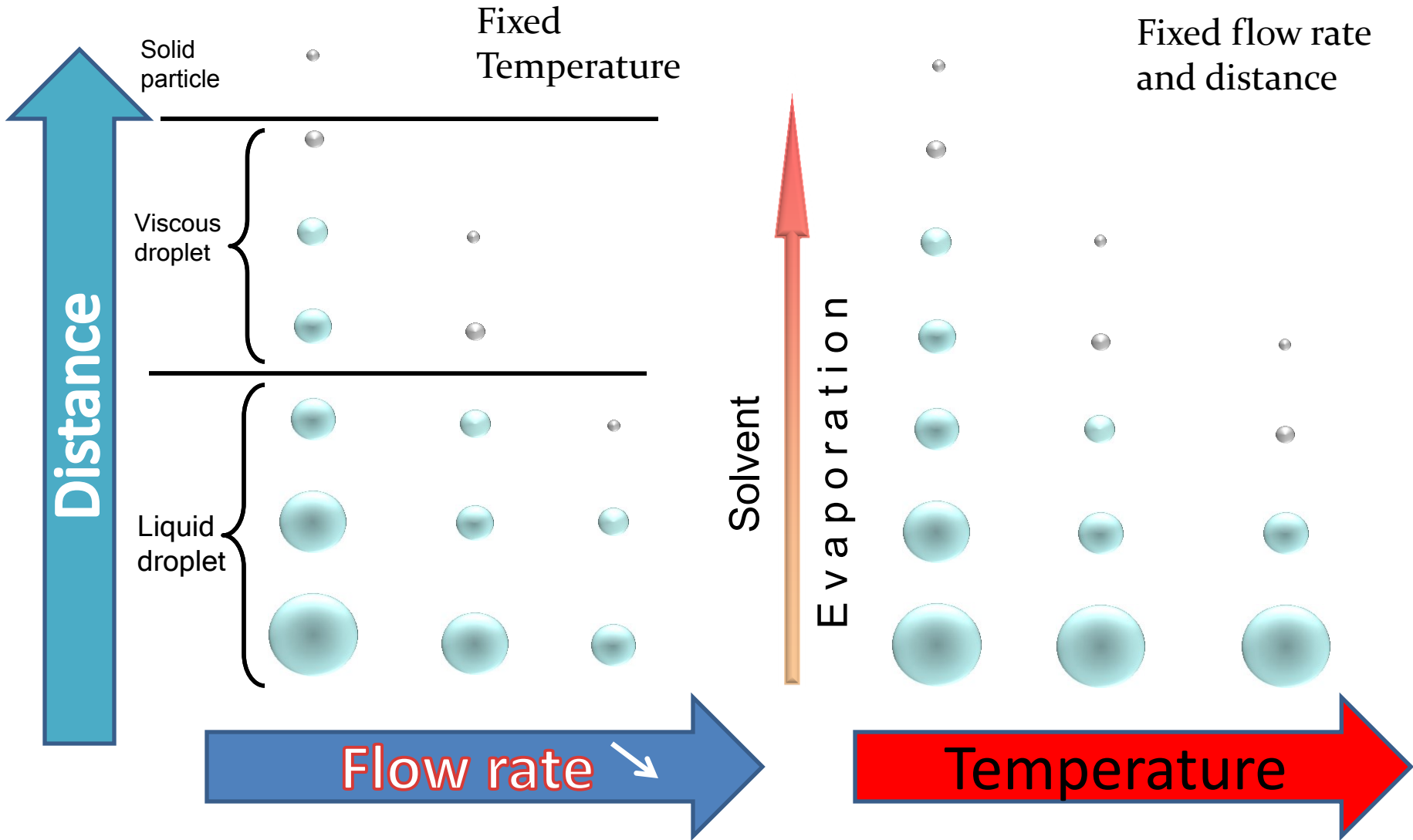
ESD variable parameters:

$$275 \text{ }^\circ\text{C} \leq T \leq 450 \text{ }^\circ\text{C}$$

$$15 \text{ mm} \leq d \leq 58 \text{ mm}$$

$$0.34 \text{ mL/h} \leq Q \leq 1.59 \text{ mL/h}$$

Droplet size



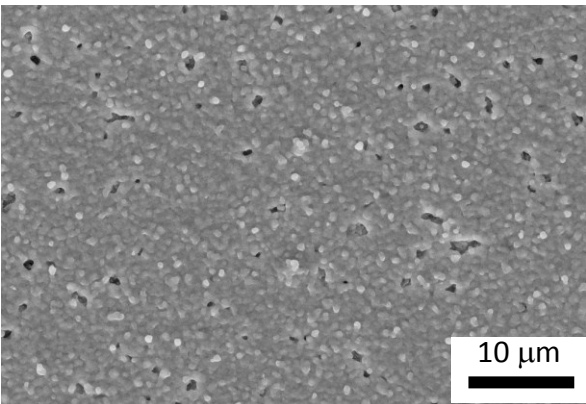
Influence of deposition parameters, Q

$T = 300\text{ }^\circ\text{C}$
 $d = 30\text{ mm}$

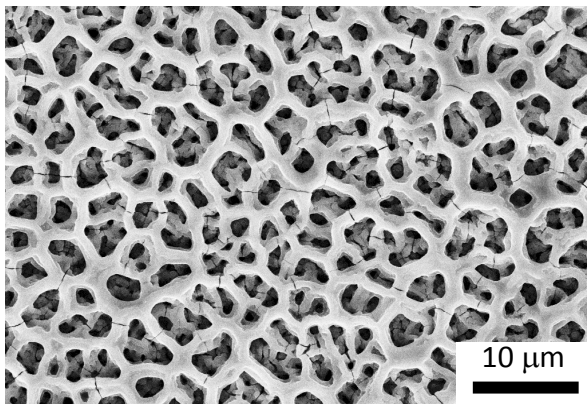
Flow rate \nearrow
droplet size \nearrow

$$\text{droplet} \propto \left(\frac{\rho \varepsilon_0 Q^3}{\gamma \sigma} \right)^{1/6}$$

0.34 mL/h



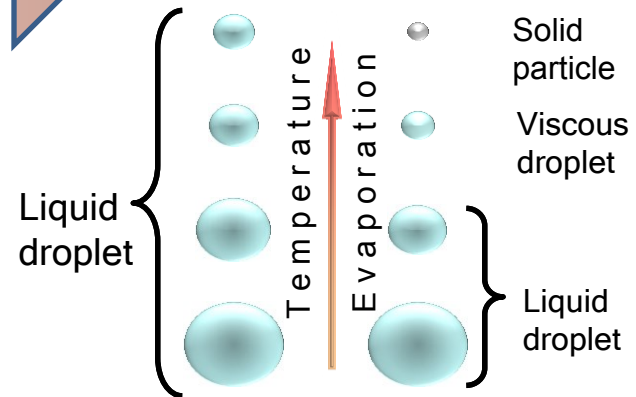
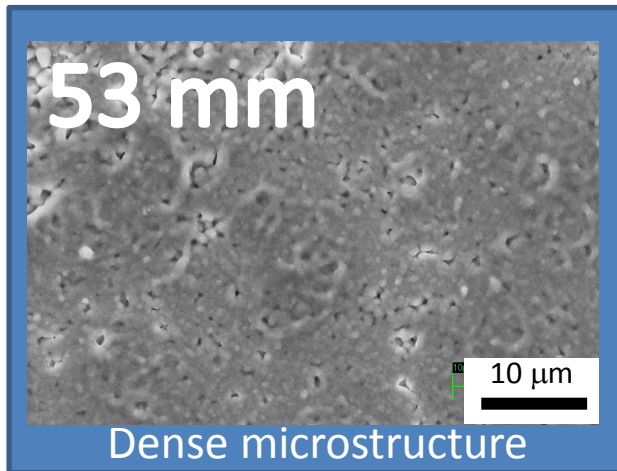
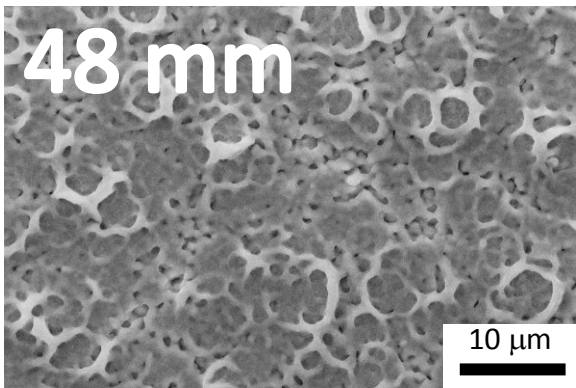
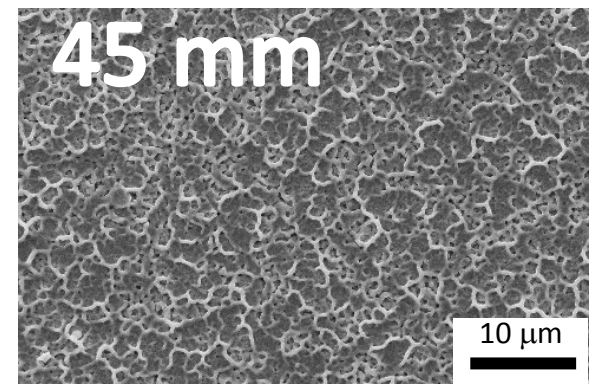
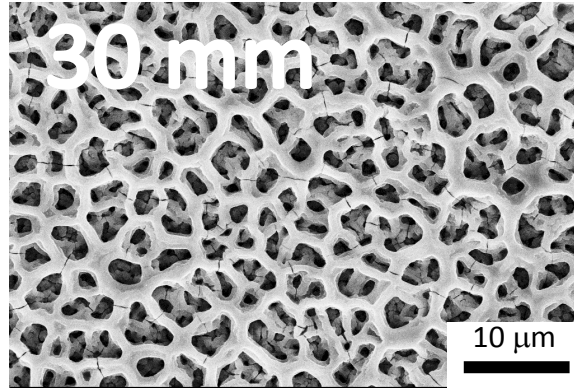
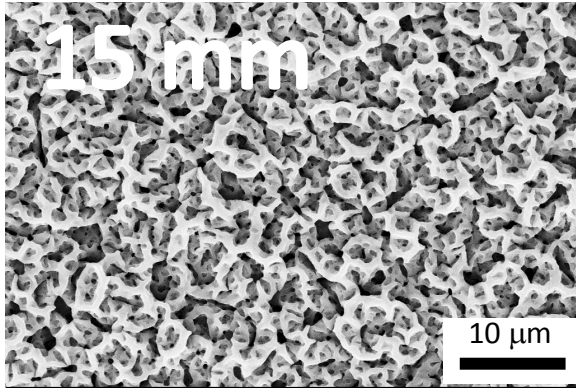
1.5 mL/h



Influence of deposition parameters, d

$T = 300\text{ }^{\circ}\text{C}$

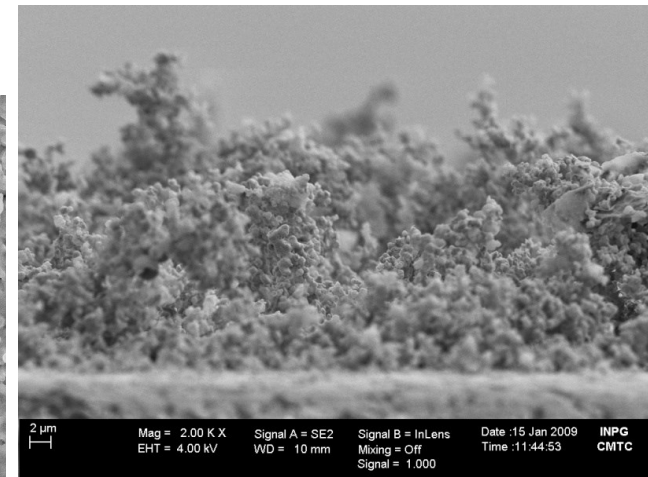
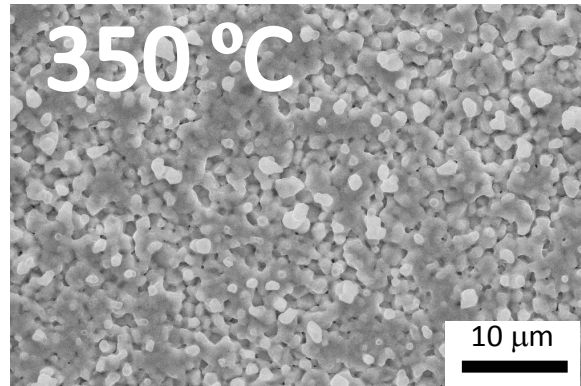
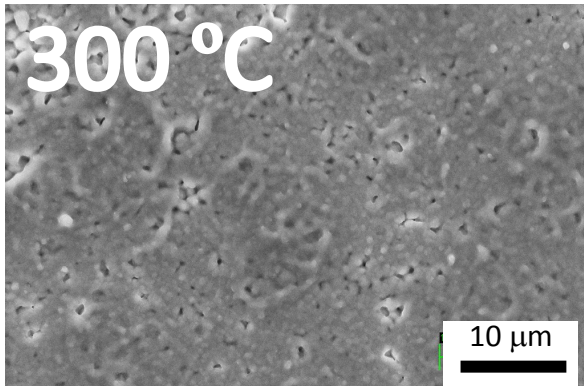
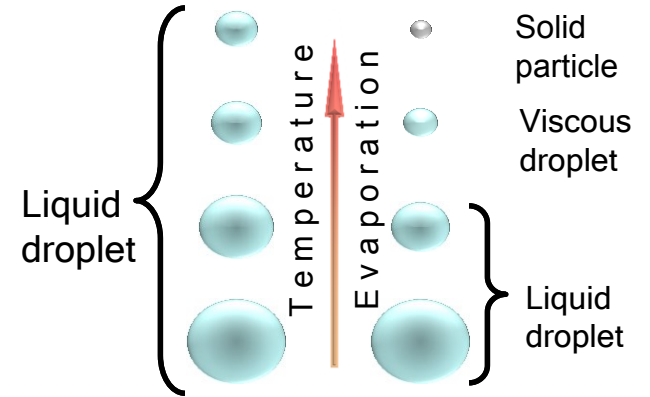
$Q = 1.5\text{ mL/h}$



Influence of deposition parameters, T

$d = 53 \text{ mm}$
 $Q = 1.5 \text{ mL/h}$

Temperature \nearrow
droplet size \searrow



Coral microstructure

Temperature, T

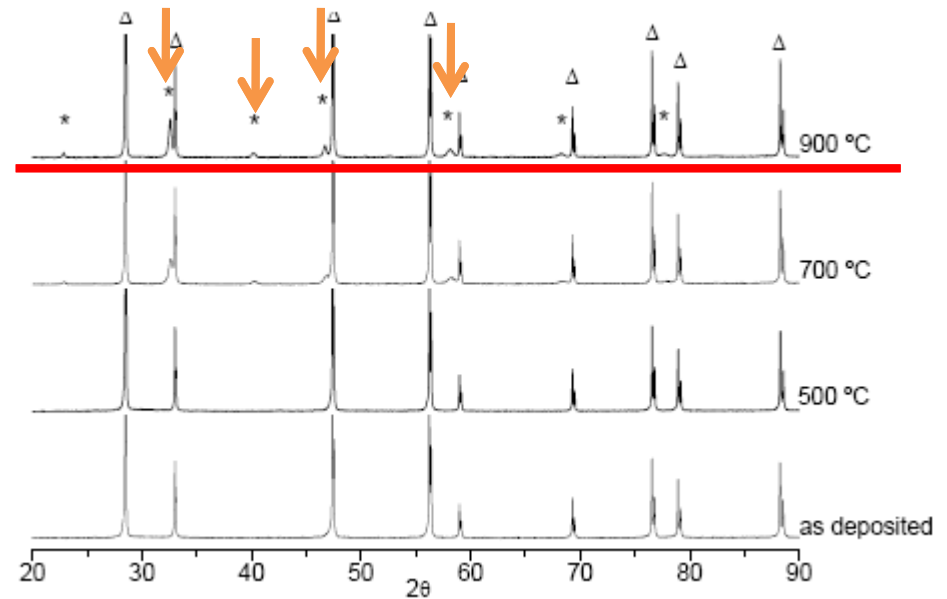
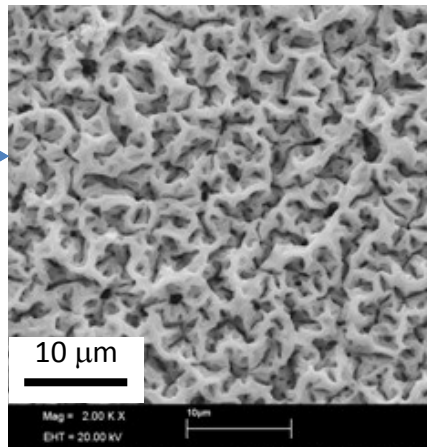
Heat Treatment

Annealing for 2h in air

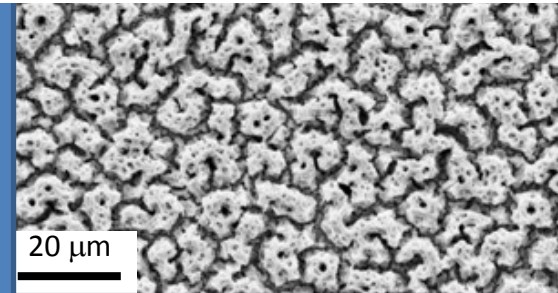
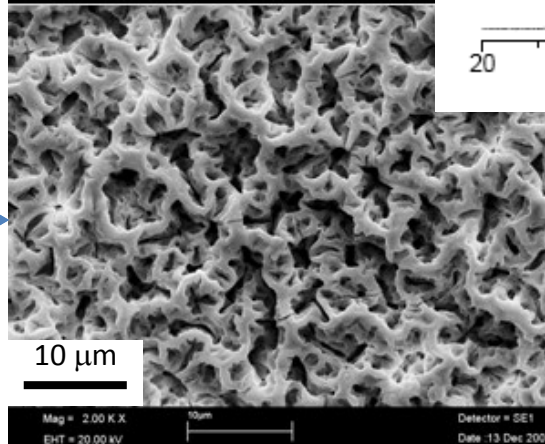
Δ - CGO
* - LSCF

1 h

$T = 300\text{ }^{\circ}\text{C}$
 $d = 15\text{ mm}$;
 $Q = 1.5\text{ mL/h}$



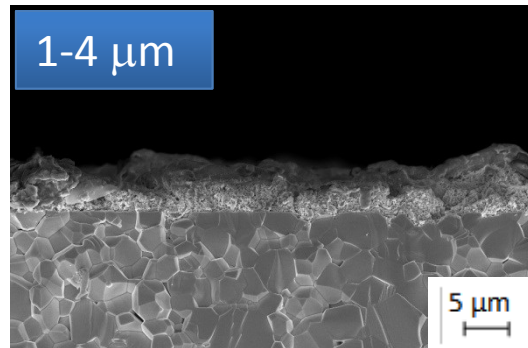
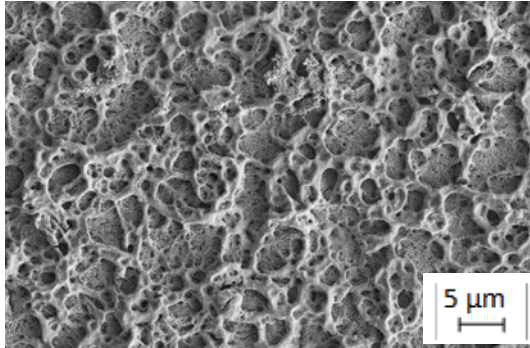
2 h



Pillar microstructure

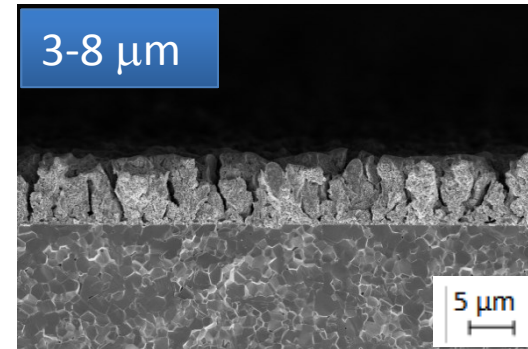
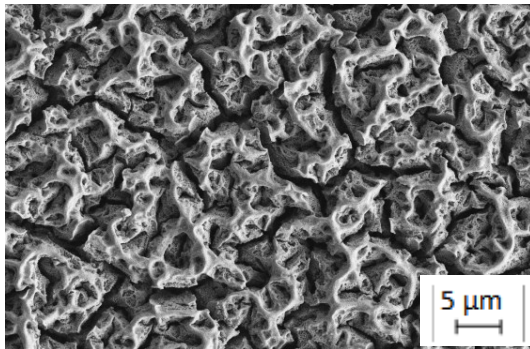
Microstructure vs. Electrochemical Performance

Dense



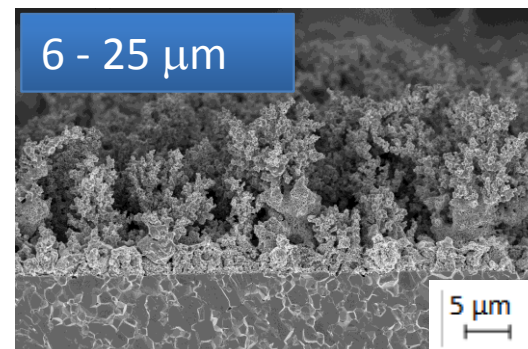
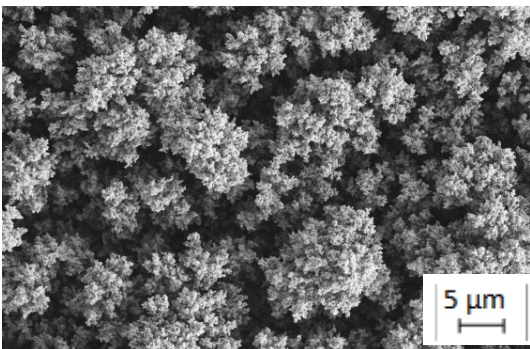
Parameters	
$T / ^\circ\text{C}$	300
$Q / \text{mL/h}$	1.59
d / mm	25 - 35
Film thickness (μm)	1 - 4

Columnar



Parameters	
$T / ^\circ\text{C}$	300 - 350
$Q / \text{mL/h}$	1.5 - 1.59
d / mm	15 - 20
Film thickness (μm)	3 - 8

Coral

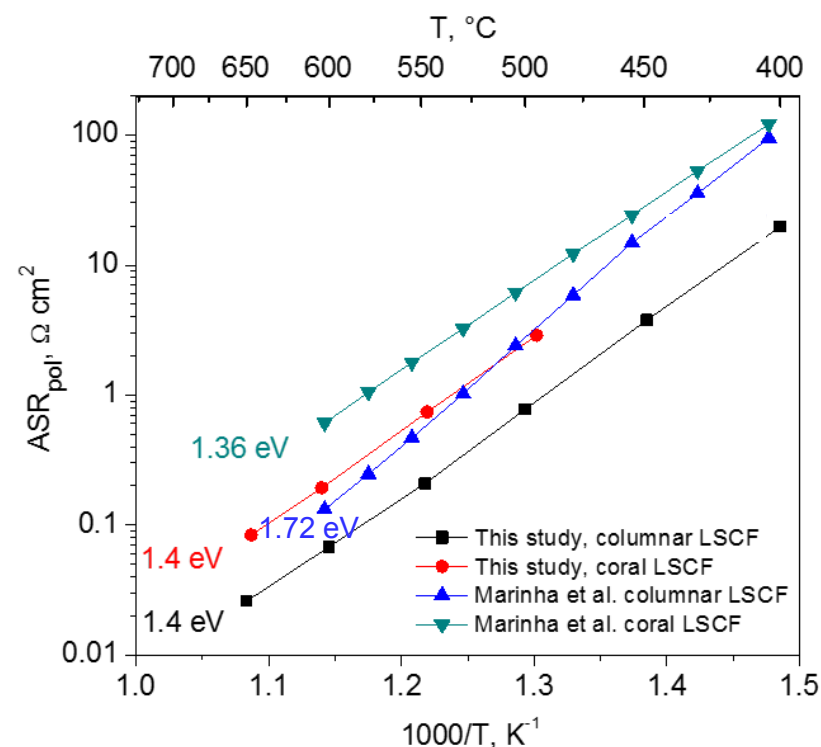


Parameters	
$T / ^\circ\text{C}$	375 - 450
$Q / \text{mL/h}$	1.02 - 1.59
d / mm	35 - 58
Film thickness (μm)	6 - 25

Influence of microstructure on LSCF electrodes

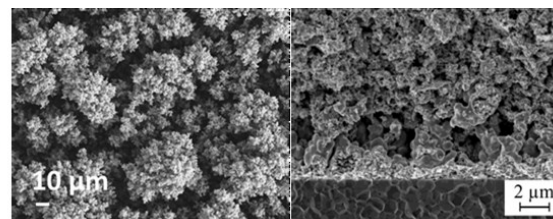
Area Specific Resistance

$$ASR_{pol} = \frac{R_{chem}}{2} \times Area_{cathode}$$



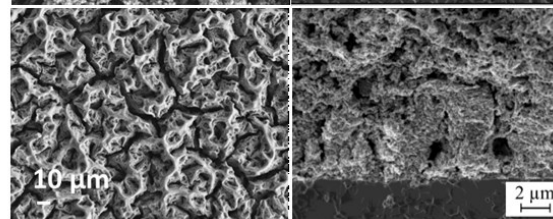
Symmetrical cell, OCV

Coral



$$a = \underline{16 \mu\text{m}^{-1}}$$

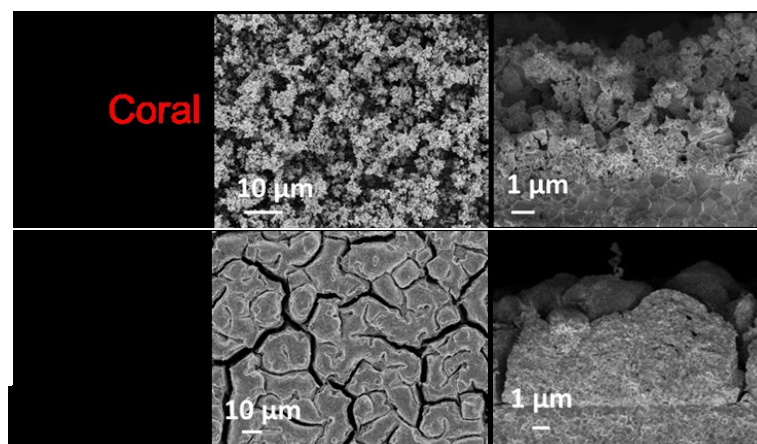
Columnar



$$a = \underline{8 \mu\text{m}^{-1}}$$

Marinha, D., PhD Thesis 2010 Grenoble INP.

Coral



$$a = \underline{19 \mu\text{m}^{-1}}$$

Celikbilek O., PhD Thesis 2016 Grenoble INP.

Influence of microstructure in LSCF columnar electrodes

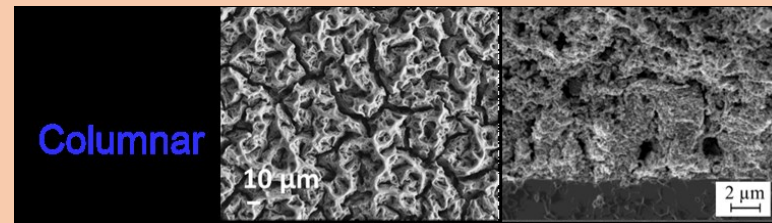
CCL by SP, KIT Karlsruhe

Static ESD

900 °C/2h, air

4-5 μm columnar width

$\text{ASR}_{\text{pol}} = 0.13 \Omega \text{ cm}^2$ at 600°C



$$a = \underline{8 \mu\text{m}^{-1}}$$

Marinha, D., PhD Thesis 2010 Grenoble INP.

D. Marinha et al, Chem. Mater. 23 [24] (2011) 5340-5348

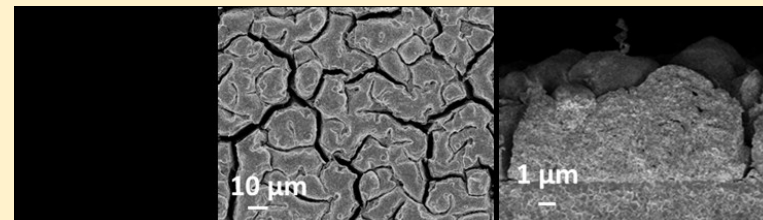
CCL by SP, LEPMI

Moving ESD

800 °C/2h, air

10-15 μm columnar width

$\text{ASR}_{\text{pol}} = 0.06 \Omega \text{ cm}^2$ at 600°C,
the best in the literature

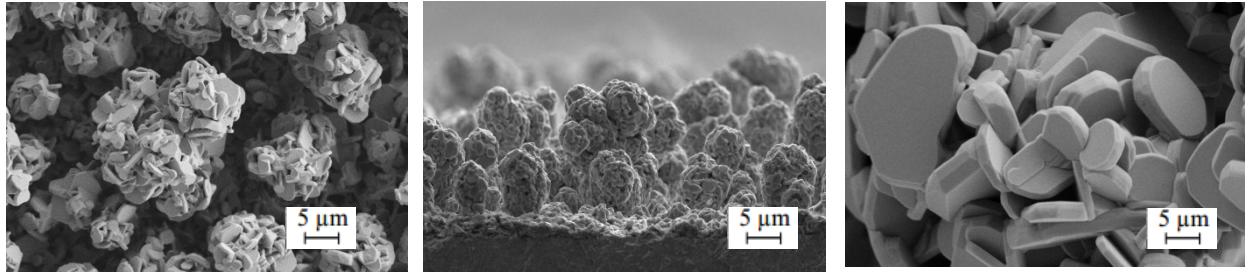


$$a = \underline{19 \mu\text{m}^{-1}}$$

Celikbilek O., PhD Thesis 2016 Grenoble INP.

O. Celikbilek et al, J. Power Sources 333 (2016) 72-82

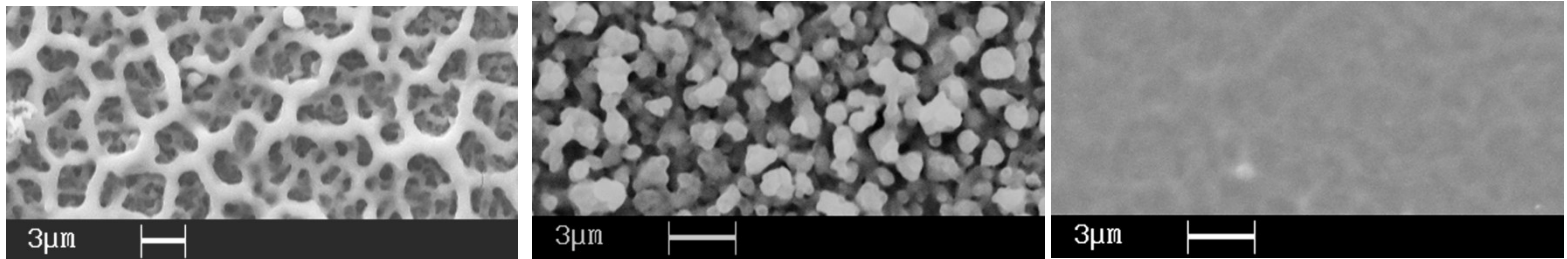
Fabrication by ESD of advanced oxygen electrodes for SOFC



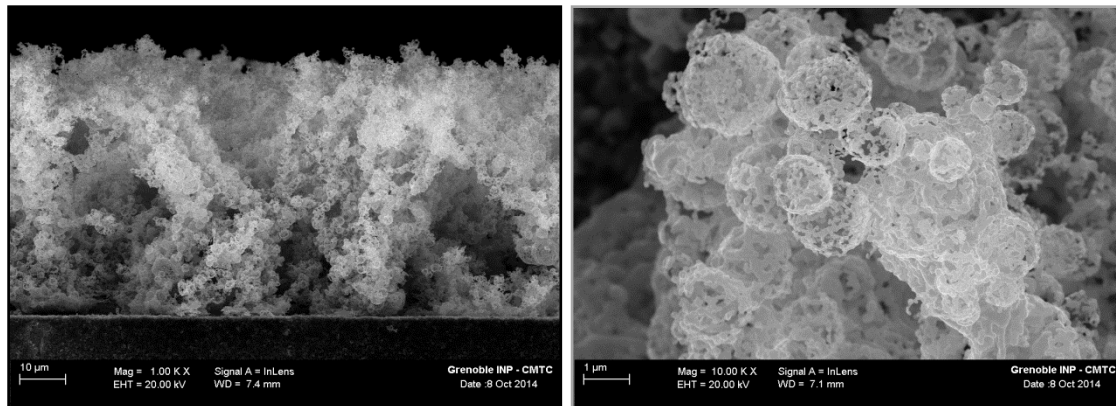
E. Djurado et al., *Solid State Ionics* 2016, 286, 102.



Composite: LSM + YSZ



A. Princiville, et al., *Chemistry of Materials*, 2005, 17, 1220..



R. Sharma, et al., *Mater. Chem. A*, 2016, 4, 12451.

Outline

1 - Sonochemistry for the synthesis of controlled nanostructured oxide powders: zirconia and ceria-based oxides

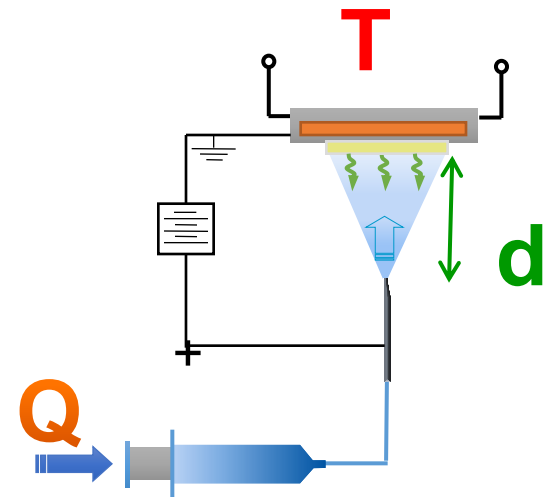
- » Ultrasonic Spray Pyrolysis (USP) process – DOE
- » CGO and TZP as electrolyte materials for IT-SOFCs
- » ZrO₂ - based powders: morphology and phase transitions
- » Physico-chemical properties of CGO powders and sintering behavior
- » USP advantages and disadvantages

2 – Electrostatic Spray Deposition for the design of dense and porous films

- » Electrostatic Spray Deposition (ESD) process
- » Optimization study of the ESD process to coat thin dense zirconia-based films
- » Fundamental study of the formation of the ESD layer
- » Advanced oxygen electrodes for SOC:
LSCF, CCO, LSM, LSM/YSZ, LPNO
- » **ESD advantages and disadvantages**

ESD advantages and disadvantages

- ✓ Tailored morphology and composition
- ✓ Porosity control independently of grain size
- ✓ Good adhesion
- ✓ Simple and low cost process
- ✓ Deposition in air
- ✓ Large choice of precursors
- ✓ Low deposition temperature
- ✓ Good reproducibility
- ✓ Double injection (composite)
- ✓ Large number of dependent parameters
- ✓ Thermal treatment after deposition to get crystallization
- ✓ Interpenetration of layers





The
E N D

Thank you for your attention

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